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Docket No.: N9460.0018/P018
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hisayuki Takasu, et al.

Examiner: H. V. Le

Application No.: 10/705,845

Confirmation No.: 4874

Filed: November 13, 2003

Art Unit: 1752

For: A METHOD OF DEVELOPING A RESIST
FILM AND A RESIST DEVELOPMENT
PROCESSOR

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

This paper is in response to the restriction requirement set forth in the Office Action mailed September 10, 2004, Applicants hereby provisionally elect Group I, which includes claims 1, 4-5, 7 and 9, for continued examination without traverse. An action on the merits of all the claims and a Notice of Allowance thereof are respectfully requested.

Dated: October 12, 2004

Respectfully submitted,

By 

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